

ABSTRACT OF THE DISCLOSURE

A wafer edge exposure apparatus is provided with an optical section for radiating exposure light onto the edge of a semiconductor wafer. The optical section is provided with a focus sensor for sensing a distance from the lower end of the optical section to the edge of the semiconductor wafer. There is provided a position control mechanism for moving the optical section vertically on the basis of a value detected by the focus sensor such that the distance matches a focal distance of the optical section.